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08/28/2002 10/022,297

(FILE 'HOME' ENTERED AT 13:26:38 ON 28 AUG 2002)

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FILE 'REGISTRY' ENTERED AT 13:28:23 ON 28 AUG 2002
L1
              1 SEA ABB=ON PLU=ON ALUMINUM/CN
L2
              1 SEA ABB=ON PLU=ON ALUMINIUM/CN
L3
              1 SEA ABB=ON PLU=ON COPPER/CN
              2 SEA ABB=ON PLU=ON (L1 OR L2 OR L3)
L4
     FILE 'HCAPLUS' ENTERED AT 13:30:28 ON 28 AUG 2002
        1306106 SEA ABB=ON PLU=ON ALUMINIUM OR ALUMINUM OR AL OR MOLTEN OR
L5
                PYROPHORIC
L6
         266346 SEA ABB=ON PLU=ON (L1 OR L2)
L7
        1318543 SEA ABB=ON PLU=ON L5 OR L6
        1010019 SEA ABB=ON PLU=ON COPPER OR CU OR L3
         200164 SEA ABB=ON PLU=ON (LAND OR LAYER##### OR COAT##### OR
                FILM#####) AND L8
L10
         88123 SEA ABB=ON PLU=ON SUBSTRATE AND L7
L11
         158301 SEA ABB=ON PLU=ON SEMICONDUCT####### (1A) DEVICE
L12
         414584 SEA ABB=ON PLU=ON SEMICONDUCT######
L13
         785234 SEA ABB=ON PLU=ON CHIP OR LEAD OR FRAME
L14
         38315 SEA ABB=ON PLU=ON RECTANG###### OR (RIGHT(3A)ANGLE##)
L15
           2622 SEA ABB=ON PLU=ON L13 AND L14
L16
           5155 SEA ABB=ON PLU=ON SOLDER#######(3A)(LAYER#### OR FILM##### OR
                COAT####)
L17
         104881 SEA ABB=ON PLU=ON (SYNTHET####### OR ARTIFIV#######) (3A) (EPOX
                ### OR RESIN OR THERMOPLASTIC#### OR ELASTOMER## OR RUBBER OR
                ADHESIVE##)
L18
        1076578 SEA ABB=ON PLU=ON EPOX### OR RESIN OR THERMOPLASTIC#### OR
                ELASTOMER## OR RUBBER OR ADHESIVE##
          52067 SEA ABB=ON PLU=ON POLYIMIDE OR POLYIMIDO
L19
L20
           5353 SEA ABB=ON PLU=ON IMIDO OR IMIDE###(2A)POLYMER###
          82659 SEA ABB=ON PLU=ON RESIN###(3A)(LAYER##### OR FILM### OR
L21
                COAT###)
L22
          10331 SEA ABB=ON PLU=ON L10 AND L9
L23
         158301 SEA ABB=ON PLU=ON L11 AND L12
L24
           1144 SEA ABB=ON PLU=ON L22 AND L23
              1 SEA ABB=ON PLU=ON L24 AND L15
                D BIB AB 1
           1143 SEA ABB=ON PLU=ON L24 NOT L25
L26
L27
             25 SEA ABB=ON PLU=ON L26 AND L16
             25 SEA ABB=ON PLU=ON L27 AND (L16 OR L17 OR L18 OR L19 OR L20
L28
                OR L21 OR POLYMER OR HOMOPOLYMER OR COPOLYMER)
              1 SEA ABB=ON PLU=ON L28 AND L17
L29
                D BIB AB 1
             24 SEA ABB=ON PLU=ON L28 NOT L29
L30
L31
             24 DUP REM L30 (0 DUPLICATES REMOVED)
                D BIB AB 1-24
L32
          17091 SEA ABB=ON PLU=ON L23 AND (L16 OR L17 OR L18 OR L19 OR L20
                OR L21 OR POLYMER OR HOMOPOLYMER OR COPOLYMER)
             25 SEA ABB=ON PLU=ON L32 AND L15
L33
             25 SEA ABB=ON PLU=ON L33 NOT L28
O SEA ABB=ON PLU=ON L34 AND L10
L34
L35
L36
             O SEA ABB=ON PLU=ON L34 AND L9
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## 08/28/2002 10/022,297

L37	2		ABB=ON		L34	AND	L7
			IB AB 1-2	2			
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L38	23	SEA	ABB=ON	PLU=ON	L34	NOT	L37
L39	0	SEA	ABB=ON	PLU=ON	L38	AND	T8
L40	0	SEA	ABB=ON	PLU=ON	L38	AND	L16
L41	0	SEA	ABB=ON	PLU=ON	L38	AND	(L16 OR L17)
L42	23	DUP	REM L38	(0 DUPL	ICATI	ES RE	EMOVED)
		D B	IB AB 1-2	23			
L43	23	SEA	L42				
L44	0	SEA	ABB=ON	PLU=ON	L43	NOT	L34
L45	23	SEA	L42				
L46	24	SEA	L31				
L47	23	SEA	ABB=ON	PLU=ON	L45	NOT	L46

L25 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2002 ACS

AN 2000:570164 HCAPLUS

DN 133:143451

TI Ceramic **substrate** for preventing deformation caused by heat stress in power transistors

IN Kwon, Heung-kyu

PA Samsung Electronics Co., Ltd., S. Korea

SO Repub. Korea, No pp. given CODEN: KRXXFC

Patent

LA Korean

FAN.CNT 1

DT

PATENT NO. KIND DATE APPLICATION NO. DATE

PI KR 9710110 B1 19970621 KR 1994-19573 19940809

AB At the center of the ceramic base material made of **rectangular**Al203, at least one slot is formed. And 2 seats are formed on the base

material to install semiconductor devices such as a power transistor. The wiring pattern and semiconductor chip are bonded to wire. At the bottom of the base material on which wiring pattern is formed, a heat sink thin film made of high conductive metal, such as Cu, Al, and Ag is formed for a better adhesion with heat sink. Therefore, by forming slot on the ceramic base material, deformation caused by heat stress or mech. reason can be prevented.

L29 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2002 ACS 1967:468678 HCAPLUS ΑN DN 67:68678 Semiconductor devices ΤI Matsushita Electronics Corp. PA SO Fr., 6 pp. CODEN: FRXXAK DTPatent French LA FAN.CNT 1 KIND DATE APPLICATION NO. DATE PATENT NO. \_\_\_\_\_ -----FR 1457006 19661028 PRAI JP 19641026 Two or more electrodes of a semiconductor device are connected to the leads of a tight capsule by using a transparent and insulating substrate on which a metallic thin film is deposited. The metallic thin-film pattern is so designed that its extreme points correspond to the semiconductor electrodes. At first the back face of the semiconductor is soldered to the metallic socket of the capsule, then the transparent and insulating substrate is superposed on the semiconductor, the 2 surfaces are bonded together, and the leads of the capsule are soldered to the thin film deposited on the transparent substrate. The capsule is made tight by applying a synthetic resin or a low-melting glass. As the semiconductor, a transistor of the planar or mesa type is used. This semiconductor can be also of an integrated-circuit type. Another possibility is to use a band of evenly spaced semiconductors on which an insulating substrate band with deposited thin-film patterns is superposed and bonded. Then, the band is cut into small pieces which each represent an independent semiconductor circuit, and these are connected sep. to the tight capsules. The transistor is soldered to its socket with a Au alloy. On the glass of quartz substrates, the metallic thin film (of Pt, In, Au, Cu, Al, Ag, or certain of their alloys) is deposited by a vacuum procedure with the use of the masking technique. The whole system is soldered to the transistor by thermocompression bonding in an inert gas atm. Before bonding, the extreme points of the metallic thin film are superposed, precisely, on the transistor electrodes by controlling their position under a microscope, which is faciliated by the substrate transparency. The lateral sides of the substrate are provided with 2 semicircular notches anticipated for the passage of capsule leads.

The leads are fixed to the thin **film** by applying a soft solder. In such a way, it is possible to avoid the earlier encountered difficulties when working with classic wire-lead connections.

08/28/2002 10/022,297

L31 ANSWER 1 OF 24 HCAPLUS COPYRIGHT 2002 ACS 2002:392083 HCAPLUS AN DN 136:394356 TI

Method of forming solder bumps on integrated circuit substrate

Hu, Chu-Chin IN

Taiwan PA

U.S. Pat. Appl. Publ., 8 pp. SO CODEN: USXXCO

DT Patent

English LA

FAN.CNT 1

APPLICATION NO. DATE KIND DATE PATENT NO. \_\_\_\_\_ -----US 2001-796268 20010228 US 2002060160 A1 20020523 PRAI TW 2000-89117431 A 20000829

The method first deposits a medium layer on a protective layer of the integrated circuit (IC) package substrate, which has good adherence ability to both the Cu layer and the protective layer. A CVD process is applied to deposit a Cu layer on the medium layer to form the metal layer. A dry film is formed on the metal layer and several contact windows are opened. A metal pad and a bump are electroplated in the contact windows. Then remove the dry film, the bumps are protruded out of the substrate with a predetd. height to be solder bumps with an IC chip. By said method, an IC chip no longer needs to form bumps thereon anymore and saves cost and reduces pitch between bumps down to 150 .mu.m. Package size is scaled for smaller IC chips and for smaller component dimension.

APPLICATION NO. DATE PATENT NO. KIND DATE \_\_\_\_

PΙ US 6380062 B1 20020430 US 2001-802796 The present invention relates to a method of manufq. semiconductor AΒ ball grid array package with metal peg leads, all connected by trace lines. The ball grid array package has internal trace lines and exposed metal pegs. A metal substrate is provided. Electroplated layers are formed over metal peg regions and a die pad region on the surface of the metal substrate. A layer of substrate material at the top surface of the metal substrate is removed so that thickness of the metal substrate is reduced. Hence, trace lines, die pad and internal metal pegs are formed. A die is attached to the die pad and elec. connections from the die to the internal metal pegs are made. A molding process is carried out to enclose the die, the die pad and the internal metal pegs on 1 side of the metal substrate with plastic material. The lower surface of the metal substrate is etched to form external metal pegs while exposing the mold material and the bottom surface of the die pad. The internal metal pegs and the external metal pegs are interconnected via the trace lines. A soldering mask layer is formed over the package surface covering the trace lines but exposing the electroplated at the end face of each external metal peg.

RE.CNT 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

## 08/28/2002 10/022,297

- L31 ANSWER 3 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2002:592468 HCAPLUS
- TI Power modules, composite **substrates** for modules thereof, and brazes applied to composite formation thereof
- IN Suzuki, Kiyomitsu; Abe, Teruyoshi; Kondo, Yasuo; Watabe, Noriyuki; Suzumura, Takashi; Nakagawa, Kazuhiko
- PA Hitachi Ltd., Japan; Hitachi Cable, Ltd.
- SO Jpn. Kokai Tokkyo Koho, 6 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

- PI JP 2002222905 A2 20020809 JP 2001-16821 20010125
- The title power modules comprise a ceramic substrate provided with a circuit layer on the front surface and a heat-releasing plate on the rear surface, a heat sink substrate bound to the heat-releasing plate with a 1st metallic braze, and a semiconductor power component bound to the circuit layer with a 2nd metallic braze. The one of the 1st and 2nd brazes is a Ag-alloy (m.p. 500-600.degree.) chosen from Ag-Cu-Sn, Ag-Cu-In, or Ag-Cu-Sn-In and the other is a solder. The use of the braze combination gives the formation of the modules minimized binding strain and reliable binding.

08/28/2002 10/022,297

L31 ANSWER 4 OF 24 HCAPLUS COPYRIGHT 2002 ACS

2002:486560 HCAPLUS AN

DN 137:40364

TI Power semiconductor devices

Morita, Koji; Murai, Takayuki; Yoshikawa, Takao ΙN

Yamaha Motor Co., Ltd., Japan PΑ

Jpn. Kokai Tokkyo Koho, 3 pp. SO

CODEN: JKXXAF

Patent DΤ

Japanese LA

FAN.CNT 1

JP 2002184907 TO APPLICATION NO. DATE \_\_\_\_\_\_

JP 2002184907 A2 20020628 JP 2000-379569 20001214 PΙ The title devices have a semiconductor chip mounted and packaged AB

on an Al substrate pad and sealed with a polymer, wherein the devices are connected via a solder layer on the Cu pad. The arrangement gives the devices simplified and increased chip packaging.

L31 ANSWER 5 OF 24 HCAPLUS COPYRIGHT 2002 ACS

AN 2002:273331 HCAPLUS

DN 136:317783

TI Ceramic circuit boards comprising ceramic insulating substrates and metal sheets for semiconductor devices

IN Sasaki, Yasuhiro; Terao, Shinya

PA Kyocera Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE
PI JP 2002111211 A2 20020412 JP 2000-296940 20000928

AB Ceramic circuit boards are manufd. by joining Al- or Cu
-based metal sheets to ceramic insulating substrates through a
solder joining layer to form wiring layer(s)
or heat sink, wherein the centerline av. roughness (Ra) of the joining
surface between the ceramic insulating substrates and the metal
sheets is 0.05-10 .mu.m and a 1-10 .mu.m thick metal layer
having excellent wettability with the solder is formed on the ceramic
circuit boards. The ceramic insulating substrates are made from
Al203, AlN, and/or Si3N4, and the metal layer is formed from
Al, Ni, or Cu.

## 08/28/2002 10/022,297

- L31 ANSWER 6 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2002:193572 HCAPLUS
- DN 136:240083
- TI Insulative ceramic substrates, manufacturing, and powersemiconductor multilayer circuit boards using substrates thereof
- IN Ishiwatari, Hiroshi; Tanaka, Akira; Taniguchi, Yasuhiko; Shimizu, Toshio; Hiramoto, Hiroyuki; Komorita, Hiroshi; Nanami, Takayuki
- PA Toshiba Corp., Japan
- SO Jpn. Kokai Tokkyo Koho, 13 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

- PI JP 2002076214 A2 20020315 JP 2000-257084 20000828
- AB The title circuit boards comprise a multilayer of ceramic substrates which are provided on their both sides with a conductive layer and laminated by soldering, brazing, binding with an active metal layer, or adhering with thermal-conductive org. polymers. The insulative ceramic substrates may be made of AlN or Al2O3 in economical process. The ceramic multilayer circuit boards gives the power semiconductor devices improved insulative withstand voltage horizontally as well as perpendicularly to the lamination against high current and voltage.

- L31 ANSWER 7 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2002:301197 HCAPLUS
- DN 137:101334
- TI Fabrication of a cylindrical display by patterned assembly
- AU Jacobs, Heiko O.; Tao, Andrea R.; Schwartz, Alexander; Gracias, David H.; Whitesidest, George M.
- CS Department of Electrical Engineering, University of Minnesota, Minneapolis, MN, 55455, USA
- SO Science (Washington, DC, United States) (2002), 296(5566), 323-325 CODEN: SCIEAS; ISSN: 0036-8075
- PB American Association for the Advancement of Science
- DT Journal
- LA English
- AB The authors demonstrate fabrication of the patterned assembly of integrated semiconductor devices onto planar, flexible, and curved substrates based on capillary interactions involving liq. solder. The substrates presented patterned, solder-coated areas that acted both as receptors for the components of the device during its assembly and as elec. connections during its operation. The components were suspended in water and agitated gently. Minimization of the free energy of the solder-water interface provided the driving force for the assembly. One hundred and thirteen GaAlAs light-emitting diodes with a chip size of 280 .mu.m were fabricated into a prototype cylindrical display. It was also possible to assemble 1500 silicon cubes, on an area of 5 square centimeters, in less than 3 min, with a defect rate of .apprx.2%. Addnl. information of the fabrication of the receptor arrays, the LED's, and the Si blocks, as well as the procedures to control the surface chem. are provided at www.sciencemag.org/cgi/content/full/296/5566/323/DC1.
- RE.CNT 26 THERE ARE 26 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 8 OF 24 HCAPLUS COPYRIGHT 2002 ACS

AN 2001:611707 HCAPLUS

DN 135:161252

TI Inexpensive and reliable BGA package for high density cavity-up wire bond device connections using a metal panel, thin **film** and build up multilayer technology

IN Ho, Chung Wen

PA Thin Film Module, Inc., Taiwan

SO U.S., 11 pp. CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 6277672	B1	20010821	US 1999-389634	19990903
	US 2001046725	A1	20011129	US 2001-900558	20010709
PRAT	IIS 1999-389634	XX	19990903		

AB A new method is provided for mounting high-d. wire bond semiconductor devices. A layer of dielec. is deposited over the 1st surface of a metal panel. One or more thin film interconnect layers are then created on top of the dielec. layer. The BUM technol. allows for the creation of a succession of layers over the thin film layers The combined layers of thin film and BUM form the interconnect substrate. One or more cavities are created in the 2nd surface of the metal panel; openings through the layer of dielec. are created where the layer of dielec. is exposed. One or more wire bond semiconductor die are inserted into the cavities, are die bonded and wire bonded to the openings that were created in the layer of dielec. Openings are created in the bottom BUM layer; solder balls are inserted and attached to this BUM layer for the completion of the Ball Grid Array (BGA) package.

RE.CNT 11 THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

- L31 ANSWER 9 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- 2001:747340 HCAPLUS
- DN 135:292447
- ΤI
- Lead-free solder joints for **semiconductor devices**Tadauchi, Masahiro; Matsuo, Mie; Nakamura, Shinichi; Komatsu, Izuru; Tejima, Koichi
- Toshiba Corp., Japan PΑ
- Jpn. Kokai Tokkyo Koho, 6 pp. SO CODEN: JKXXAF
- $\mathsf{DT}$ Patent
- Japanese LA
- FAN.CNT 1

	PATENT NO.	KIND DATE		APPLICATION NO.	DATE	
ΡI	JP 2001284384	A2	20011012	JP 2000-96447	20000331	

JP 2001284384 A2 20011012 The joint comprises (a) a semiconductor substrate, (b) AΒ a conductive metal layer, (c) an alloy layer of Zn or Ag with the metal in layer b, (d) a Sn-rich layer, and (e) a Pb-free solder layer mainly consisting of Sn and contg. the said metals. Diffusion of the solder materials into the semiconductor substrates is prevented. L31 ANSWER 10 OF 24 HCAPLUS COPYRIGHT 2002 ACS AN 2001:617459 HCAPLUS

DN 135:187509

ΤI Group III semiconductor laser devices

Nagai, Seiji; Ito, Suguru; Yuguchi, Mitsuo; Koike, Masayoshi Toyota Gosei Co., Ltd., Japan Jpn. Kokai Tokkyo Koho, 13 pp. ΙN

PΑ

SO

CODEN: JKXXAF

 $\mathsf{D}\mathbf{T}$ Patent

Japanese LA

FAN.CNT 1

KIND DATE PATENT NO. APPLICATION NO. DATE

JP 2001230498 A2 20010824 JP 2000-38279 20000216 ΡI

The devices comprise: a Cu heat sink; a Sn/In solder AΒ layer; a nickel layer; a pair of Au/Mo electrodes bonding a Au/Mo/Rh anode and a Ni cathode; and a p-AlGaAs cladding, an active, an n-AlGaAs cladding, an AlN buffer and a sapphire substrate.

- L31 ANSWER 11 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2001:29155 HCAPLUS
- DN 134:94313
- TI Fabrication of wafer chip-size-package semiconductor
- IN Miyata, Masahiro; Ezawa, Hirokazu
- PA Toshiba Corp., Japan

ball formation.

- SO Jpn. Kokai Tokkyo Koho, 6 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 2001007135 A2 20010112 JP 1999-176312 19990623

AB The title fabrication wafer chip-size-package (CSP) semiconductor devices involves forming a bump electrode over a barrier metal film and an contact pad on a semiconductor substrate, coating an org. polymer film to cover the bump electrode over the entire substrate, etching back the substrate surface to expose the bump electrode, curing the org. polymer film, and forming a solder ball on the bump electrode. The bump electrode may be made of Cu, Ni, or Au which gives a good wettability to the solder

L31 ANSWER 12 OF 24 HCAPLUS COPYRIGHT 2002 ACS

AN 2000:636235 HCAPLUS

DN 133:216532

TI Fabrication of **semiconductor** component with external contact **polymer** support

IN Farnworth, Warren M.; Wood, Alan G.

PA Micron Technology, Inc., USA

SO U.S., 13 pp. CODEN: USXXAM

DT Patent

LA English

FAN CNT 1

I AN.	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 6118179	A	20000912	US 1999-384783	19990827
	US 6180504	В1	20010130	US 1999-440380	19991115
PRAI	US 1999-384783	A3	19990827		

A semiconductor component includes a substrate, bonding pads on the substrate, and external contacts bonded to the bonding pads. Exemplary external contacts include solder balls, solder bumps, solder columns, TAB bumps and stud bumps. Preferably the external contacts are arranged in a dense array, such as a ball grid array (BGA), or fine ball grid array (FBGA). The component also includes a polymer support member configured to strengthen the external contacts, absorb forces applied to the external contacts, and prevent sepn. of the external contacts from the bonding pads. In a first embodiment, the polymer support member comprises a cured polymer layer on the substrate, which encompasses the base portions of the external contacts. In a second embodiment, the polymer support member comprises support rings which encompass the base portions of the external contacts. In either embodiment the polymer support member transfers forces applied to the external contacts away from the interface with the bonding pads, and into the center of the contacts.

RE.CNT 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

- L31 ANSWER 13 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2000:197893 HCAPLUS
- DN 132:211606
- Copper sheet-joined nitride ceramic substrates having TIhigh reliability for semiconductor devices
- IN Uchida, Shinji
- Fuji Electric Co., Ltd., Japan PΑ
- Jpn. Kokai Tokkyo Koho, 7 pp. SO CODEN: JKXXAF
- $\mathsf{D}\mathbf{T}$ Patent
- Japanese LA
- FAN.CNT 1

JP 2000086368 PATENT NO. KIND DATE

JP 2000086368 A2 20000328 JP 1998-261177 19980916 PΙ

A braze layer from Cu, Ag, or Cu-Ag type AΒ alloys contg. active metals is formed on nitride ceramic substrates, and the braze layer is joined with Cu sheets by soldering to obtain nitride ceramic substrates for semiconductor devices. The nitride ceramic plates are AlN or Si3N4 sintered plates.

- L31 ANSWER 14 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 1999:719059 HCAPLUS
- DN 131:331076
- TI Cast metal seal for semiconductor substrates
- IN Toy, Hilton T.; Bolde, Lannie R.; Covell, James H., II; Edwards, David L.;
  Goldmann, Lewis S.; Gruber, Peter A.
- PA International Business Machines Corporation, USA
- SO U.S., 10 pp. CODEN: USXXAM
- DT Patent
- LA English
- FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE

- PI US 5982038 A 19991109 US 1997-850092 19970501
- The invention relates generally to a new scheme of providing a seal for semiconductor substrates and chip carriers. More particularly, the invention encompasses a structure and a method that uses a multilayer metallic seal to provide protection to chips on a chip carrier. This multilayer metal seal provides both enhanced hermeticity lifetime and environmental protection. For the preferred embodiment, the multilayer metallic seal is a 2-layer solder structure which is used to create a low-cost, high-reliability, hermetic seal for the module. This solder structure has a thick high-m.p. region that is attached to a cap, and a thin interconnecting region of lower m.p. for sealing the substrate to the cap.
- RE.CNT 24 THERE ARE 24 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

L31 ANSWER 15 OF 24 HCAPLUS COPYRIGHT 2002 ACS AN 1999:610940 HCAPLUS DN 131:236653 ΤI Copper-beryllium alloy lead for semiconductor device showing high resistance to peeling from solder under Uno, Takao ΙN Furukawa Electric Co., Ltd., Japan PAJpn. Kokai Tokkyo Koho, 5 pp. SO CODEN: JKXXAF DT Patent Japanese LA FAN.CNT 1 PATENT NO. KIND DATE APPLICATION NO. DATE ----\_\_\_\_\_\_ JP 11260993 A2 19990924 JP 1998-61126 19980312 ΡI The lead is made of a Cu alloy contg. 0.2-3.0 wt.% of Be and AΒ having a Zn layer or a Cu-Zn alloy layer (contg. .gtoreq.10 wt.% of Zn) at a part to be soldered. The Cu alloy may further contain 0.001-5.0 wt.% (as total) of Ni, Co, Fe, Si, Pb, Al, Zr, Mg, Ag, and/or Te in addn. to Be. By arranging the Zn layer or the Cu-Zn alloy layer, adhesion strength of the Cu-Be alloy to Pb solder is improved.

- L31 ANSWER 16 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 2000:651912 HCAPLUS
- DN 133:328110
- TI 3D Si-on-Si stack package
- AU Kanbach, H.; Wilde, J.; Kriebel, F.; Meusel, E.
- CS DaimlerChrysler AG, Research & Technology, Lab Microelectronics, Frankfurt/Main, D-60528, Germany
- SO Proceedings of SPIE-The International Society for Optical Engineering (1999), 3830(International Conference on High Density Packaging and MCMs, 1999), 248-253
  CODEN: PSISDG; ISSN: 0277-786X
- PB IMAPS International Microelectronics and Packaging Society
- DT Journal
- LA English
- Future electronic systems have to satisfy an increasing demand in respect AB of: Small vol., lightwt., operation at high frequencies and speed, high power levels, sensitive and smart functions and cost effectiveness. An attractive approach for meeting these requirements is the 3-dimensional (3D) electronic packaging. Starting from the state of the art this paper presents a new concept of 3D-electronic packaging. The approach can be described as a Si-on-Si multi chip module flip chip technol. with arrays of fine etched and filled vertical elec. interconnections (vias). In contrast to existing concepts our concept uses area arrays of vias with a high no. of interconnections and not only peripheral interconnections. A 3D Si-on-Si stack package demonstrator has been realized. The demonstrator (12.5 .times. 12.5 .times. 2.3 mm3) consists of 4 Sisubstrates each representing a system level and contg. 4 thinned and as flip chip assembled chips. In the outer part of the Sisubstrates there are 3 rows of vertical interconnections each with a diam. of 110 .mu.m and a length of 500 .mu.m. The vias are isolated, metalized and coated with WTi/Cu/Au. The chips are flip chip mounted in the flat side of the Si-substrates on appropriate pads and metal layers. When interconnecting the Sisubstrates to each other by bump technol. the chips submerge into cavities on the rear side of the adjacent Si-substrate. Altogether there are 12 chips integrated in the 3D-stack package demonstrator. The chips also test the technol. and quality of the electronic packaging. For this purpose they contain a set of thin film heaters, junctions for temp. measuring, Al-meanders for stress and strain measuring and daisy chains for conduction paths controlling. Key technologies are anisotropic reactive ion etching, metalization, filling of the vias and the flip chip technol. with solder or polymer bumps.
- RE.CNT 11 THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

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ANSWER 17 OF 24 HCAPLUS COPYRIGHT 2002 ACS
      1998:398503 HCAPLUS
AN
      129:75005
DN
ΤI
      Electronic component and semiconductor device, method
      for manufacturing and mounting thereof, and circuit board and electronic
      equipment
IN
      Hashimoto, Nobuaki
      Seiko Epson Corporation, Japan; Hashimoto, Nobuaki
PA
      PCT Int. Appl., 73 pp.
      CODEN: PIXXD2
DT
      Patent
      Japanese
LA
FAN.CNT 2
                          KIND DATE
                                                    APPLICATION NO.
      PATENT NO.
                                                                         DATE
                                  _____
                                                    -----
                          _---
                                                  WO 1997-JP4437
      WO 9825297
ΡI
                          A1
                                  19980611
                                                                         19971204
          W: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, HU, ID, IL, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

RW: GH, KE, LS, MW, SD, SZ, UG, ZW, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG
      CN 1206494
                                                    CN 1997-191450
                                  19990127
                                                                         19971008
                           Α
     AU 9851363
                           A1
                                  19980629
                                                    AU 1998-51363
                                                                         19971204
     CN 1210621
                                                    CN 1997-192032
                           Α
                                  19990310
                                                                         19971204
PRAI JP 1996-339045
                           Α
                                  19961204
      JP 1996-356880
                           Α
                                  19961226
      JP 1997-91449
                           Α
                                  19970326
     WO 1997-JP4437
                           W
                                  19971204
AΒ
     A semiconductor device whose package size is nearly
     the same as the size of a chip, which has a stress absorbing layer
      , which does not require a flexible substrate, and which can be
     manufd. in a large no. at the same time. A method for manufg. a
      semiconductor device includes a process wherein
      electrodes are formed on a wafer, a process wherein a resin
      layer is formed as a stress reducing layer on the wafer
      except for the parts where the electrodes are formed, a process wherein a
     Cr layer is formed as an interconnect on the whole surface of
     the wafer including the electrodes and the resin layer
      , a process wherein solder balls are formed as external
     electrodes on parts of the chrome layer which are formed on the
     resin layer, and a process wherein the wafer is diced to
      semiconductor chips. In the processes for forming the chrome
      layer and for forming the solder balls, a metal thin film
     deposition technol. used in the wafer process of semiconductor
     manufg. is employed.
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L31 ANSWER 18 OF 24 HCAPLUS COPYRIGHT 2002 ACS

AN 1997:341032 HCAPLUS

DN 127:27514

TI Manufacture of **semiconductor device** having solder bump electrode

IN Kanda, Koji

PA Sanyo Electric Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 09097792 A2 19970408 JP 1995-251449 19950928

The title method involves the following steps; (A) opening an elec. insulating film to reach a metal pad on a semiconductor substrate, (B) forming an Al-plated electrode film, (C) forming a barrier metal film on the electrode film, (D) forming a photoresist film, (E) plating to form a solder bump electrode on the metal pad, (F) removing the photoresist film, (G) treating the plated electrode film with an alkali developer, and (H) reflowing the bump electrode. The electrode with good stable elec. characteristics and dimensional stability was obtained.

L31 ANSWER 19 OF 24 HCAPLUS COPYRIGHT 2002 ACS

AN 1996:508827 HCAPLUS

DN 125:156246

TI Manufacture of bump electrode

IN Wakabayashi, Takeshi; Abe, Akihiko

PA Casio Computer Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

film on a substrate, forming a layer for
formation of a metal underlayer on the protective film and a
contact pad in a hole of the protective film, forming a
50-150-.mu.m plating resist layer, and forming a solder
columnar bump electrode in the hole. A bump electrode with enough height
was obtained.

- L31 ANSWER 20 OF 24 HCAPLUS COPYRIGHT 2002 ACS
- AN 1994:225049 HCAPLUS
- DN 120:225049
- TI Sintered aluminum nitride substrate having metalized layers
- IN Ogata, Yasunobu; Yoshizoe, Sumio
- PA Hitachi Metals Ltd, Japan
- SO Jpn. Kokai Tokkyo Koho, 3 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE
PI JP 06032687 A2 19940208 JP 1992-190363 19920717

The AlN substrate has multiple metalized layers and a solder layer as the outmost layer. The formation of multiple metalized layers improves solder wettability and solder adhesion.

L37 ANSWER 2 OF 2 HCAPLUS COPYRIGHT 2002 ACS AN 1967:495180 HCAPLUS DN 67:95180 TΙ Encapsulated multi-terminal semiconductor devie Hill, John ΙN PΑ International Standard Electric Corp. SO U.S., 5 pp. CODEN: USXXAM DT Patent

English LA

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE US 3324357 19670606

PATENT NO. KIND DATE

PRAI GB 19640129 A method is described for providing an encapsulated semiconductor device which includes a wafer having opposite cond. type electrodes, a header for mounting the wafer including lead wires, and solder contacts between electrodes and lead wires. Preformed n-p-n transistors formed in a slice of n-type Si with a layer of Si oxide as a diffusion mask are used as an example. Al contacts to the collector, base, and emitter regions are formed by known techniques. Au-Cr metallic film, large area contacts are formed over the Al contacts. The slice is dipped in a fluxing soln. and then in a solder bath which forms low mounds of solder on the contacts. The slice is sepd. into wafers for mounting. The header has 3 lead wires passing through a glass-metal seal and projecting on the other side. The lead wires are formed by bending these ends inward toward each other, and a flat is produced on each end. The flats are approx. coplanar and at right angles to the direction of the leads on the far side of the seal. The mounting is conducted so that the solder on each of the contacts of the wafer is in contact with the appropriate lead wire flat. The assembly is heated by radiation or other suitable means. The solder melts and wets the lead wire ends. After cooling, the assembly is washed and dried to remove any contaminants. Final encapsulation is effected by fixing a metal cap over the header by resistance "projection" welding. Alternatively, the wafer may be surrounded with a thermosetting resin which also fills the area between the wafer and the face of the header.

L42 ANSWER 1 OF 23 HCAPLUS COPYRIGHT 2002 ACS

ΑN 2002:573704 HCAPLUS

DN 137:133195

Semiconductor chip-mounting packages and fabrication ΤI of packages thereof

Omura, Kenichi IN

PA Kyocera Corp., Japan

Jpn. Kokai Tokkyo Koho, 9 pp. SO

CODEN: JKXXAF

DT Patent

Japanese LA

FAN.CNT 1

PΙ

AΒ

JP 2002217327 KIND DATE APPLICATION NO. DATE PATENT NO. KIND DATE JP 2002217327 A2 20020802 JP 2001-8916 20010117 The title packages comprise an insulator plate having a large rectangular through-hole in its central region for mounting a semiconductor chip, a pl. no. of circuit conductors provided on the upper surface of the insulator plate, ground and power

circuit conductors provided on the lower surface of the insulator plate, a thermosetting polymer insulator layer covering over the ground and power circuit conductors, and a heat-releasing plate adhered to the insulator plate via the polymer insulator layer. The polymer insulator layer is recessed by 0.05-2 mm from its large rectangular through-hole edges so that the circuit conductors and the chip electrodes are secured for connection without excess insulator.

- L42 ANSWER 2 OF 23 HCAPLUS COPYRIGHT 2002 ACS
- AN 2002:566153 HCAPLUS
- DN 137:118035
- TI Screen printing masks and method for mounting **semiconductor** parts on circuit substrates using them
- IN Ikari, Takashi; Hirano, Masato; Yamaguchi, Atsushi
- PA Matsushita Electric Industrial Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 6 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
0000011154		00000731	TD 0001 15740	00010104

PI JP 2002211154 A2 20020731 JP 2001-15742 20010124

AB The mask, useful for supplying an adhesive material to substrate lands or electrode pads with a narrow pitch on semiconductor parts, has a plurality of through holes including those having oval and/or rectangular cross sections perpendicular to the thickness direction, wherein shapes of the lands or electrode pads may be identical to the cross sections. The method is esp. useful for fabricating BGA (ball grid array) and/or CSP (chip size package).

L42 ANSWER 3 OF 23 HCAPLUS COPYRIGHT 2002 ACS

2002:349916 HCAPLUS AN

TΙ Semiconductor device and its production method. [Machine Translation].

IN

Kasuya, Yasumasa Rohm Co., Ltd., Japan PΑ

Jpn. Kokai Tokkyo Koho, 7 pp. SO CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

r Alv.	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PΙ	JP 2002134677	A2	20020510	JP 2000-322207	20001023
	US 2002096790	A1	20020725	US 2001-27856	20011019
PRAI	JP 2000-322207	Α	20001023		
AB	[Machine Transla	tion o	of Descriptors].	Preventing the	exfoliatio
	resin package by	the n	moisture which i	nvades, it offers	the

ion of the resin package by the moisture which inva semiconductor device whose reliability is high. Semiconductor chip 1 and this semiconductor chip 1 only loading through 1st wire 11, in island through the 2nd wire 12 of the plural books 2 of the plane surface apparent abbreviation rectangular condition which is connected to semiconductor chip 1 electrically and semiconductor chip 1 it has with the plural inner leads/reads 3 which each one electrically are connected, semiconductor chip 1 being the semiconductor device S which the resin package is done when the underside of island 2 is exposed with the packaging resin, in the marginal vicinity of island 2, the underside 2b side cuts and is lacked and from the other part makes thin in thickness direction thin 5 It is formed, the slit 9 which is penetrated to the thickness direction is formed to thin 5.

L42 ANSWER 4 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2002:349910 HCAPLUS Semiconductor device and its production method. [Machine Translation]. Fujimoto, Hiroaki; Sahara, Ryuichi; Minamio, Masaki; Fukuda, Toshiyuki; Nomura, Toru Matsushita Electric Industrial Co., Ltd., Japan PA Jpn. Kokai Tokkyo Koho, 16 pp. SO CODEN: JKXXAF DT Patent LA Japanese FAN.CNT 1 KIND DATE APPLICATION NO. DATE PATENT NO. \_\_\_\_ -----\_\_\_\_\_ JP 2002134661 A2 20020510 JP 2000-326602 20001026 [Machine Translation of Descriptors]. That light weight conversion had PΙ AΒ become problem in accordance with the demand of small size light weight conversion of the electronic equipment, regarding the semiconductor device of BGA type. It possesses wiring electrode 1 in the surface, the wiring baseplate the **semiconductor chip** 4 where is loaded onto the surface of 3 which possesses ball

electrode 1 in the surface, the wiring baseplate the semiconductor chip 4 where is loaded onto the surface of 3 which possesses ball electrode 2 in the base and wiring baseplate 3 and semiconductor chip the metal thin line from the insulated seal resin 6 where seals the surface of 5 which connects with the wiring electrode 1 of 4 and wiring baseplate 3 and wiring baseplate 3 it is constituted, the surface periphery of seal resin 6 seal resin 6 being deleted, has had hypotenuse section 10, when cubic measure of seal resin 6 of abbreviation rectangular parallelepiped form of imagination is designated as 100 % ], inside that 20 % ] The seal resin above is deleted. Because of this the seal resin quantity of the surface periphery is reduced substantially, weight is made to decrease, the semiconductor device of lightweight

BGA type is actualized as a whole.

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L42 ANSWER 5 OF 23 HCAPLUS COPYRIGHT 2002 ACS
     2002:273582 HCAPLUS
AN
    Resin seal type semiconductor device and its
     production method. [Machine Translation].
IN
    Aoyama,
              Tomoyuki
    Matsushita Electric Industrial Co., Ltd., Japan
PA
    ·Jpn. Kokai Tokkyo Koho, 7 pp.
SO
    CODEN: JKXXAF
\mathsf{DT}
     Patent
LA
     Japanese
FAN.CNT 1
     PATENT NO. KIND DATE
                                          APPLICATION NO. DATE
                     ----
     _____
    JP 2002110728 A2 20020412 JP 2000-304569 20001004 [Machine Translation of Descriptors]. Until recently in as for the
PΙ
ΑB
     semiconductor device to be rectangular
     condition, to become large, the lead/read frame itself
     which is loaded large as a plane surface form, as for the small-sized
     resin seal type semiconductor device there was
     a theme that call by result it cannot be actualized. In spherical
     semiconductor device the point opposing 10 and that
     semiconductor device 10, the plural inner lead
     /read sections 4 which are arranged and each inner lead/read
     section the metal thin line 8 which connects with the electrode 11 of the
     surface of 4 and semiconductor device 10 and
     semiconductor device 10, inner lead/read
     section 4, the seal resin to connect 12 which seals the outside
     surrounding territory in metal thin line 8 and inner lead/read
     section 4, to be constituted from the outer lead/read section 5
    which is exposed from seal resin 12, because spherical
     semiconductor device 10 is used, to hold down the
     enlargement of plane surface form, more small-sized resin seal
     type semiconductor device It can actualize.
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L42 ANSWER 6 OF 23 HCAPLUS COPYRIGHT 2002 ACS
    2001:314144 HCAPLUS
ΑN
ΤI
    Semiconductor device
    Horie, Yoshitaka; Maeda, Masahide
ΙN
    Rohm Co., Ltd., Japan
PA
    PCT Int. Appl.
SO
    CODEN: PIXXD2
DT
    Patent
    Japanese
LA
FAN.CNT 1
                                        APPLICATION NO. DATE
    PATENT NO. KIND DATE
    WO 2001031704 A1
PΙ
                           20010503
                                        WO 2000-JP6858 20001002
        W: CN, KR, US
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
            PT, SE
                                          JP 2000-126742
     JP 2001196518
                     A2
                           20010719
                                                          20000427
    TW 459279
                     В
                           20011011
                                         TW 2000-89120630 20001004
PRAI JP 1999-306341
                     Α
                           19991028
    JP 2000-126742 A
                          20000427
    A semiconductor device (S1) comprising a
AB
    semiconductor chip (5), a chip mounting
     internal lead (1) for mounting the semiconductor
     chip (5), chip connecting internal leads (2,
     3) electrically connected to the upper surface of the
     semiconductor chip (5), and a resin package
     (7), rectangular as seen in a plan view, enclosing the
     semiconductor chip (5) and internal leads
     (1-3). The end of the chip mounting internal lead (1)
     is a rectangle or substantially rectangle extending
     longitudinally of the resin package (7).
             THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD
             ALL CITATIONS AVAILABLE IN THE RE FORMAT
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L42 ANSWER 7 OF 23 HCAPLUS COPYRIGHT 2002 ACS

AN 2001:758791 'HCAPLUS

TI Semiconductor device and a method of manufacturing the same

IN Masuda, Masachika; Wada, Tamaki; Nishizawa, Hirotaka; Kagaya, Koich Iro

PA Japan

SO U.S. Pat. Appl. Publ. CODEN: USXXCO

DT Patent

LA English

FAN CNT 1

I AN.	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2001031513	A1	20011018	US .2001-826965	20010406
PRAI	JP 2000-114352	Α	20000414		

AB A semiconductor device comprising: a resin sealing body, plural semiconductor chips situated inside the resin sealing body and formed of rectangular -shaped plane surfaces, having a first main surface and second main surface facing each other, and having electrodes disposed on the first side of a first side and a second side of the first main surface, the first side and second side facing each other, and leads having inner parts situated inside the resin sealing body and outer parts situated outside the resin sealing body, the inner parts being electrically connected to the electrodes of the plural semiconductor chips via bonding wires, wherein: the first main surfaces are aligned in the same direction with their respective first sides situated on the same side, and the plural semiconductor chips are laminated in positions offset with respect to one another such that the electrodes of one of the mutually opposite semiconductor chips are situated further outside than the first sides of the other semiconductor chips.

L42 ANSWER 8 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2001:404187 HCAPLUS AN ΤI Semiconductor device manufacturing method, press die and guide rail including forming a crack perpendicular to an extension of the sealing resin Aoki, Hideji; Sekiya, Hidenori; Katou, Kenichirou; Nishitani, Hiromu IN Mitsubishi Denki Kabushiki Kaisha, Japan; Mitsubishi Electric Engineering PA Co., Ltd. U.S., 36 pp. SO CODEN: USXXAM DTPatent English LA FAN.CNT 1 LIS 6242207 US 6242287 B1 20010605 US 1998-44928 19980320 PRAI JP 1997-270887 A 19971003 Provided are a method for manufacturing a semiconductor device in which a sealing resin is prevented from being damaged and generation of a resin piece is suppressed, a press die for suppressing the generation of the resin piece, and a quide rail. A frame receiving die (11) includes a cavity (11d) having a rectangular contour shape seen on a plane which serves to house a sealing resin (3) therein, and a remaining gate housing section (11c) provided on any of four corners of the cavity (11d) corresponding to a remaining gate (3b) on a lower face of a corner (2a) of

provided in a boundary portion between the cavity (11d) and the remaining

(3b) is housed in the remaining gate housing section (11c). THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD RE.CNT 6

resin (3) is housed in the cavity (11d) and the remaining gate

a lead frame (2). A lower gate punch (11a) is

gate housing section (11c). When the lead frame (2) is mounted on the frame receiving die (11), the sealing L42 ANSWER 9 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2001:927930 HCAPLUS AN Lead/read frame and semiconductor TIdevice. [Machine Translation]. ΙN Takaike, Kazuo Shinko Electric Industries Co., Ltd., Japan PA Jpn. Kokai Tokkyo Koho, 6 pp. SO CODEN: JKXXAF DT Patent Japanese LA FAN.CNT 1 JP 2001359275 KIND DATE APPLICATION NO. DATE PATENT NO. JP 2001358275 A2 20011226 JP 2000-180858 20000616 PΙ [Machine Translation of Descriptors]. The  ${\bf semiconductor}$ AB component being the concave section where the loading aspect which the loading is done was formed to the base, with usual diaphragm processing squeezes the deep concave section, in the extent of being and the formation difficult the formation it is possible in the heat radiation board with processing, at the same time can prevent the exfoliation of the heat radiation board and the seal resin easily effectively is the lead/read frame is offered. Semiconductor component 12 of said heat radiation board 18 the loading aspect which the loading is done, squeezes the inner lead/read 24 which is connected electrically semiconductor component 12 of rectangular condition the semiconductor component 12 which the loading is done and by wire 32 and the like and 24 \* \* with in the lead/read frame 10 which is possessed in the heat radiation board 18 which the loading is done and heat radiation board 18,

the formation is done in base 14 of concave section 16 of the rectangular condition which was formed by processing at the same

time the bending part which the inner wall section of each angular section of concave section 16 the formation is done, pulls out and is dropped in

penetration hole is formed 26 and 28.

L42 ANSWER 10 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2001:760781 HCAPLUS AN Production method of the substrate and the semiconductor ΤI device which uses this. [Machine Translation]. Enzan, Takao; Sasaki, Atsuo; Nokita, Kanta; Ishihara, Masamichi Mitsui High-Tec, Inc., Japan IN PΑ Jpn. Kokai Tokkyo Koho, 8 pp. SO CODEN: JKXXAF DT Patent LA Japanese FAN.CNT 1 PATENT NO. KIND DATE APPLICATION NO. DATE KIND DATE \_\_\_\_\_\_ \_\_\_\_\_ JP 2001291795 A2 20011019 JP 2000-106961 20000407 PΙ [Machine Translation of Descriptors]. In the semiconductor AΒ device of flip tip/chip type of resin seal type, not yet filling up of the seal resin at the time of resin seal and occurring of void are prevented. As has of rectangular base material 2 the rectangular semiconductor chip loading territory 3 all over, the specified wiring pattern which from semiconductor chip loading territory 3 is expanded in outside direction is done, the formation with the insulated layer the covering doing the whole surface which excludes the land 5 of the wiring pattern, the formation does in the gate territory with all of the semiconductor chip loading territory 3 which is connected 17 which becomes, the filler inlet of the seal resin of the insulated layer in the baseplate 1 A which becomes, and the gate territory as thin section 6 A, the formation does with the other parts as thick section 6 B.

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L42 ANSWER 11 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2001:727470 HCAPLUS AN Production method of lead/read frame and ΤI semiconductor device. [Machine Translation].
Yasunaga, Hisashi; Sugimoto, Atsushi ΙN Mitsui High-Tec, Inc., Japan PA SO Jpn. Kokai Tokkyo Koho, 7 pp. CODEN: JKXXAF DT Patent Japanese LA FAN.CNT 1 KIND DATE APPLICATION NO. PATENT NO. \_\_\_\_\_ \_\_\_\_\_ JP 2001274308 A2 20011005 JP 2000-82091 20000323 [Machine Translation of Descriptors]. As penetration of the resin to lead/read of back side is prevented, when cutting off in each PΙ semiconductor device, exfoliation of lead/read and the seal resin is prevented. Through tie bar 6, combines the unit frame 2 which and possesses the lead/read 2 r of the feature which surrounds tip/chip loading limits 2 B in each side of rectangular plane surface plural gathers and the unit frame aggregate guide rail 5 g and the guide rail 5 g which are provided furthermore to outside tesseral of notch 5 S and the notch 5 S which were formed to outside tesseral of peripheral tie bar 6 o and the peripheral tie bar 6 o where combines unit **frame** 2 to the peripheral section of 7 which is formed and unit **frame** aggregate 7 and the combined piece 5 r which combines with peripheral tie bar 6 o forms lead/read Doing form processing of frame, 5 unit frame aggregate including with the portion of 7 and guide rail and 5 g the lumping together doing excluding back resin seals forms, this the cutting separation it does tie bar 6 and alongside with peripheral tie bar 6 o.

L42 ANSWER 12 OF 23 HCAPLUS COPYRIGHT 2002 ACS AN 2001:357365 HCAPLUS Lead/read frame and semiconductor

device and the production method. [Machine Translation].

Yugawa, Masayuki IN

Matsushita Electronics Corp., Japan PA

SO Jpn. Kokai Tokkyo Koho, 7 pp. CODEN: JKXXAF

heat radiation board 12.

DT Patent

LA Japanese

FAN.CNT 1

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JP 2001135766 TIND DATE APPLICATION NO. DATE , PATENT NO. JP 2001135766 A2 20010518 JP 1999-313421 19991104 [Machine Translation of Descriptors]. The case where the resin seals the lead/read frame which the semiconductor component the loading is done occurrence of void is retarded. In the underside of the point of plural inner leads /reads 11, heat radiation board 12 through insulated resin layer 13, is kept, semiconductor component 14 is mounted in the central part of heat radiation board, 12 is connected the electrode by the wire 16 where the point of 15 which is provided on the semiconductor component and inner lead/read 11 consists of the gold and the like. And, penetration hole 17 of spindle condition

or rectanglular condition is provided in the corner section of

, 😲

ANSWER 13 OF 23 HCAPLUS COPYRIGHT 2002 ACS L42 2001:281335 HCAPLUS ΑN Semiconductor luminous device. [Machine Translation]. TIMamoru IN Maekawa, Rohm Co., Ltd., Japan PΑ Jpn. Kokai Tokkyo Koho, 5 pp. SO CODEN: JKXXAF Patent DT LA Japanese FAN.CNT 1 APPLICATION NO. DATE PATENT NO. KIND DATE -----JP 1999-289606 19991012 PΙ JP 2001111115 A2 20010420 [Machine Translation of Descriptors]. Offer the tip/chip type AΒ luminous device which is made the constitution which improves the brightness of the direction which is parallel with mounted direction without receiving the condition to the automated implementation. Semiconductor luminous device 10, the baseplate is formed notch 7 X and 8 X on 2 which the formation is done and the baseplate on the both ends, electrode pattern for the abbreviation center section of 3 of the pair where one terminal 3 X and 4 X cover aforementioned notch, 4 and the baseplate surface the luminous die (LED) tip/chip 1st translucent resin mold 6 A of the condition which seals 1 which the loading is done and the aforementioned LED tip/chip and, has with the 2nd translucent resin mold 6 B of the rectangular condition which is arranged in the

surrounding. As 1st index of refraction of the translucent resin

resin, extending resident in can point to the both ends section of

2nd translucent resin mold to the end of baseplate 2.

is selected 2nd more largely than index of refraction of the translucent

L42 ANSWER 14 OF 23 HCAPLUS COPYRIGHT 2002 ACS

AN 2002:78366 HCAPLUS

DN 136:111355

...

TI Semiconductor device to emit heat from a semiconductor chip to a mother board

IN Lee, Seon Gu; Han, Im Taek

PA Amkor Technology Korea, Inc., S. Korea

SO Repub. Korean Kongkae Taeho Kongbo, No pp. given

CODEN: KRXXA7
Patent

LA Korean

FAN.CNT 1

DT

PATENT NO. KIND DATE APPLICATION NO. DATE

KR 2000019224 A 20000406 KR 1998-37202 19980909

PΙ A semiconductor device is provided to emit heat from a semiconductor chip to a mother board and be capable of encapsulating by using a transfer molding. A semiconductor device comprises: a flat-board heat spreader having a rectangular spreader penetrating portion in the center; a printed circuit board (PCB) having a board penetrating portion connected with the spreader penetrating portion while the heat spreader adheres to the PCB by inserting an adhesive; a sub-heat spreader elongated and adhered to a bottom surface of the board penetrating portion by thermal conductive solder; a semiconductor chip adhered to inside of the board penetrating portion of the PCB, the top surface of the sub-heat spreader; wire for connecting the semiconductor chip with the PCB; encapsulant filled up in the board penetrating portion of the PCB and the spreader penetrating portion of the heat spreader to protect the semiconductor chip and the wire from the exterior circumstances; and solder balls for having the mother board elec. communicate with the semiconductor chip while being adhered to the bottom surface of the PCB.

08/28/2002 10/022,297

L42 ANSWER 15 OF 23 HCAPLUS COPYRIGHT 2002 ACS

2000:769684 HCAPLUS AN

133:343402 DN

Manufacture of resin-packaged semiconductor TΙ devices

Sukekawa, Hirokazu; Yoshida, Isamu; Amano, Yasuo Hitachi Maxell, Ltd., Japan; Hitachi, Ltd. IN

PΑ

Jpn. Kokai Tokkyo Koho, 6 pp. SO CODEN: JKXXAF

Patent

DTJapanese LA

FAN.CNT 1

 $\zeta_i$ 

PATENT NO. KIND DATE APPLICATION NO. DATE \_\_\_\_

JP 1999-116715 19990423 JP 2000306935 A2 20001102 PΙ

Bump contacts are formed on resp. pads of semiconductor AB devices, rectangular plate-shaped leads are connected across the bump contacts for each pad, and the semiconductor devices and the base of lead terminals are molded by thermosetting resins.

08/28/2002 10/022,297

L42 ANSWER 16 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2000:741353 HCAPLUS ΑN 133:303293 DN TI Semiconductor LED devices, semiconductor photosensor devices and array Yanagase, Masashi; Konishi, Yasuhiro; Imamoto, Hiroshi; Takaoka, Motoaki; IN Yama, Yoshikazu Omron Corp., Japan Jpn. Kokai Tokkyo Koho, 22 pp. PΑ SO CODEN: JKXXAF  $\mathsf{DT}$ Patent LA Japanese FAN.CNT 1 APPLICATION NO. DATE PATENT NO. KIND DATE JP 2000294831 A2 20001020 JP 1999-101894 19990408 PΙ

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L42 ANSWER 17 OF 23 HCAPLUS COPYRIGHT 2002 ACS 2000:687757 HCAPLUS ΑN Semiconductor device. [Machine Translation]. TI IN Suzuki, Takeshi PA Toshiba Corp., Japan SO Jpn. Kokai Tokkyo Koho, 10 pp. CODEN: JKXXAF DT Patent LA Japanese FAN.CNT 1 APPLICATION NO. DATE KIND DATE PATENT NO. JP 2000269395 A2 20000929 JP 1999-73062 19990318 PΙ [Machine Translation of Descriptors]. Improving the heat dissipation, AB improves allowance loss, offers the semiconductor device which can prevent the thermal destruction of the component. Besides the fact that outside outside in mold was connected 2 of the rectangular condition which the resin seals the tip/ chip where semiconductor circuit was formed and aforementioned semiconductor circuit and was formed to the one side of outer circle of mold, 2 possesses specified lead/read width in lead/read terminal was connected 4 and semiconductor circuit and was formed to the aforementioned one side, possesses the lead/read width of 4 times that or more aforementioned specified lead/read width in lead/read terminal is connected 6 and semiconductor circuit and opposes to the aforementioned one side outside was formed to the side, possesses the lead/read width of 4 times that or more aforementioned specified lead/read width has possessed with lead/read terminal 8.

L42 ANSWER 18 OF 23 HCAPLUS COPYRIGHT 2002 ACS

AN 2000:666433 HCAPLUS

ΤI Surface mounted type semiconductor device. [Machine Translation].

Masahiro; Tsuboi, Yoshiji IN Ootomo,

Toshiba Corp., Japan PA

Jpn. Kokai Tokkyo Koho, 4 pp. SO CODEN: JKXXAF

the area is expanded.

DΤ Patent

LA

**,**)

Japanese FAN.CNT 1 APPLICATION NO. DATE PATENT NO. KIND DATE -----JP 2000260926 A2 20000922 JP 1999-63052 19990310 PΙ [Machine Translation of Descriptors]. The resin being lacking around the support bar is prevented, the mounted type semiconductor device which does not have the mounted error to the baseplate is offered. Semiconductor chip 4 adheres in order the die padding for back of 3 where and this die padding 3 to expose in appearance, as the aforementioned semiconductor chip is molded, the underside almost forms the rectangular mounted aspect the plastic package 2 where and the one terminal in inside aforementioned plastic package 2, is connected by aforementioned semiconductor chip 4, in order for other edge to expose in the side of aforementioned package mounted aspect 8, as is bent in the aforementioned package underside vicinity connection lead/read 10 outside and the one terminal is bonded to aforementioned die padding 3, other edge to corner section 9 of aforementioned package mounted aspect 8 In order to expose, has with the support bar 15 which is bent inside the aforementioned package, as for aforementioned exposure end 16 of this support bar, in order to occupy the corner section 9 of aforementioned package mounted aspect 8 substantially,

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L42 ANSWER 19 OF 23 HCAPLUS COPYRIGHT 2002 ACS
    2000:88745 HCAPLUS
AN
     Semiconductor device. [Machine Translation].
TI
             Nobuaki; Sano,
                                                 Shinichi
ΙN
                              Masashi; Suzuki,
    Rohm Co., Ltd., Japan
PA
     Jpn. Kokai Tokkyo Koho, 17 pp.
SO
    CODEN: JKXXAF
DT
     Patent
LA
     Japanese
FAN.CNT 2
                                        APPLICATION NO. DATE
     PATENT NO. KIND DATE
                    A2
A1
                                                          19980831
PΙ
    JP 2000040781
                           20000208
                                         JP 1998-246023
     EP 1089335
                           20010404
                                         EP 1999-918314
        R: DE, GB, NL
TW 413834 B
PRAI JP 1998-138691 A
                                         TW 1999-88108022 19990518
                           20001201
                     Α
                           19980520
     JP 1998-138692 A
                           19980520
     JP 1998-246023
                     Α
                           19980831
    WO 1999-JP2357 W
                           19990430
    [Machine Translation of Descriptors]. Degree of freedom of choice of
AΒ
    mounting direction of the semiconductor device in the
     case where the semiconductor device is mounted on the
     circuit baseplate and the like is raised. As in the resin
     package 4 which, was formed to the form of the plane surface apparent
     abbreviation rectangular condition which possesses specified
     thickness lead/read lead/read 20 inside 10 inside 1st
     the formation is done and 2nd and, continues in lead/read 10
     inside 1st as outside resin package 4 lead/read 11
     outside 1st the formation is done and, continues in lead/read 20
     inside 2nd, lead/read 21 outside 2nd was formed outside
     resin package 4 and, in the semiconductor device
     X which has, lead/read lead/read 21 outside 11 outside
     1st and 2nd, those basic ends 11 A 21 A that tried parallels to the side
     41 of resin package 4 (42), from each basic end 11 A and 21 A
     furthermore lead/read 11 each outside continues, 21 to parallel
     to the base 45 of resin package 4 tried.
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L42 ANSWER 20 OF 23 HCAPLUS COPYRIGHT 2002 ACS AN 2000:203176 HCAPLUS
TI Light radiating semiconductor device with a

TI Light radiating **semiconductor device** with a reflector [Machine Translation].

IN Ishinaga, Hiroki

PA Rohm Co. Ltd., Japan

SO Ger. Offen. CODEN: GWXXBX

DT Patent LA German

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FAN. CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI DE 19945919 A1 20000330 DE 1999-19945919 19990924

JP 2000101149 A2 20000407 JP 1998-270790 19980925

PRAI JP 1998-270790 19980925

[Machine Translation of Descriptors]. A light radiating semiconductor device contains a substrate 12. This substrate is formed with a pair electrode courses 14, 16 on it. One of the electrode courses has a rectangular line range, on which a light radiating semiconductor chip 25 is form-connected. That light radiating semiconductor chip is strength-connected on the other side with the other electrode course. A reflector is formed for spritz-Formen of a liquid crystalline polymer on the substrate over. The reflector has a passage cutout, which is formed at its central range, and which exhibits an internal surface, which is coated with a metal. That light radiating semiconductor chip is arranged, and a translucent

epoxy resin 36 with a glass transition temperature of
60.degree.C or among them into the passage cutout is filled within the
passage cutout, in order to form thereby a shroud body.

L42 ANSWER 21 OF 23 HCAPLUS COPYRIGHT 2002 ACS
AN 1999:756885 HCAPLUS
DN 131:359164
TI Semiconductor devices for photosensor component
packages
IN Sano, Masashi; Suzuki, Nobuaki; Suzuki, Shinichi
PA Rohm Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 14 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 2
PATENT NO. KIND DATE APPLICATION

FAN.CNT Z								
PAT	ENT NO.	KIND	DATE	APPLICATION NO.	DATE			
JΡ	11330131	A2	19991130	JP 1998-138692	19980520			
EΡ	1089335	A1	20010404	EP 1999-918314	19990430			
	R: DE, GB,	NL						
TW	413834	В	20001201	TW 1999-88108022	19990518			
JΡ	1998-138691	Α	19980520					
JΡ	1998-138692	Α	19980520					
JΡ	1998-246023	Α	19980831					
WO	1999-JP2357	W	19990430					
	PAT  JP EP  TW JP JP JP	PATENT NO.  JP 11330131 EP 1089335 R: DE, GB, TW 413834	PATENT NO. KIND  JP 11330131 A2  EP 1089335 A1  R: DE, GB, NL  TW 413834 B  JP 1998-138691 A  JP 1998-138692 A  JP 1998-246023 A	PATENT NO. KIND DATE  JP 11330131 A2 19991130 EP 1089335 A1 20010404 R: DE, GB, NL  TW 413834 B 20001201 JP 1998-138691 A 19980520 JP 1998-138692 A 19980520 JP 1998-246023 A 19980831	PATENT NO. KIND DATE APPLICATION NO.  JP 11330131 A2 19991130 JP 1998-138692 EP 1089335 A1 20010404 EP 1999-918314 R: DE, GB, NL  TW 413834 B 20001201 TW 1999-88108022 JP 1998-138691 A 19980520 JP 1998-138692 A 19980520 JP 1998-246023 A 19980831			

The title devices comprise a wide 1st inner lead wire having a chip-mounting dia-bonding region, a 2nd lead wire having a wire-bonding region connected via a semiconductor chip and a wire, a rectangular plastic package with a desired width for packaging in with a semiconductor chip or the 2nd inner lead wire, and a 1st outer lead wire connected to the 1st inner lead wire and formed on the outside the package. The die-bonding region is provided at a position shifted from the center of the package and the wire-bonding region is provided at the center or its proximity. The arrangement of the bonding regions avoids breaking of the wires in the package.

L42 ANSWER 22 OF 23 HCAPLUS COPYRIGHT 2002 ACS

AN 1994:568436 HCAPLUS

DN 121:168436

TI Opening window on resin film on semiconductor device

IN Kajiwara, Satomi

PA Fuji Electric Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN CNT 1

LAN	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 06140317	A2	19940520	JP 1992-284797	19921023
	JP 3151964	В2	20010403		

AB In opening a rectangular window on semicured coated resin film on a chip-installed wafer by liq.
etchant, the corners of the window-corresponding pattern of a photoresist etching mask is round off to make the radius of curvarture .gtoreq.1.5 times than the film thickness of the resin film. The resin may be polyimide, the window may be opened simultaneously with treatment of the photoresist by a developer as an etchant, and the photoresist may be dissolved out by a solvent after opening the window.

L42 ANSWER 23 OF 23 HCAPLUS COPYRIGHT 2002 ACS AN 1994:287375 HCAPLUS

120:287375 DN

TI Resin-potted semiconductor device

IN Okuaki, Yutaka

PΑ Oki Electric Ind Co Ltd, Japan

Jpn. Kokai Tokkyo Koho, 4 pp. CODEN: JKXXAF

DTPatent

LA Japanese

FAN.CNT 1

APPLICATION NO. DATE PATENT NO. KIND DATE \_\_\_\_\_ JP 05259362 A2 19931008 JP 1992-51976 19920311 PΙ

The title device employs a lead frame comprising a AΒ rectangular tab for mounting a semiconductor chip, nobs protruding through the potting resin along the long sides of the tab; and H2O-repellent coating film formed on at least 1 side of each tab.